

1    **ABSTRACT OF THE DISCLOSURE**

2           This invention is a method for cleaning a semiconductor  
3    manufacturing system, which passes a highly volatile liquid agent through the  
4    system to remove the impurities and to dissolve chemicals used in the system.  
5    The cleaning agent dissolves and washes the chemicals out of the system to  
6    keep the chemicals from combining with moisture in the air and forming oxide  
7    particles. By washing with a liquid, residual gases and impurities in the system  
8    are rapidly removed from the system. After washing the system, the cleaning  
9    agent is quickly dried because the cleaning agent is highly volatile. Thereby,  
10   the system is cleaned efficiently within a short time by using this method.